

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4	"4411735".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/10 11:19
L2	22	("3700497" "3871930" "4039371").PN. OR ("4411735").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:20
L3	22	("3700497" "3871930" "4039371").PN. OR ("4411735").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:26
L4	1	"4411735".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:39
L5	1	"4740562".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:41
L6	19	"4740562"	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:42
L7	78	(wet etch\$3 or wet-etch\$3) near10 (water or "h.sub.2" or H2O) near10 (percent or "%")	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:44
L8	32	(wet etch\$3 or wet-etch\$3) near10 (anhydrous)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:55
L9	24	((wet etch\$3 or wet-etch\$3) near10 (anhydrous)) not (HF or hydrofluoric)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:57
L10	0	((wet etch\$3 or wet-etch\$3) near10 (anhydrous)) near10 (hydroxide\$1)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:58
L11	23	((wet etch\$3 or wet-etch\$3) near10 (water or "h.sub.2") near10 (hydroxide\$1) near10 (weight or "5" or percent\$4)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:58
L12	23	((wet etch\$3 or wet-etch\$3) near10 (water or "h.sub.2") near10 (hydroxide\$1 or organic solvent) near10 (weight or "5" or percent\$4)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 12:01
L13	14	((wet etch\$3 or wet-etch\$3) near10 (water or "h.sub.2") near10 (hydroxide\$1 or organic solvent) near10 (weight or "%" or percent\$4)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 12:01

L14	24	((wet etch\$3 or wet-etch\$3) near10 (water or "h.sub.2")) near10 (hydroxide\$1 or solvent or methanol or ethanol or ammonium) near10 (weight or "%" or percent\$4)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:07
L15	1	"6849200".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:30
L16	1	"6284721".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:32
L17	2	(wet etch\$3 or wet-etch\$3) near10 ((water or "h.sub.2") adj 25%) near10 (hydroxide \$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:34
L18	0	(wet etch\$3 or wet-etch\$3) near10 (25% adj (water or "h. sub.2")) near10 (hydroxide\$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:35
L19	0	(wet etch\$3 or wet-etch\$3) near10 ("2"\$1% adj (water or "h.sub.2")) near10 (hydroxide \$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:35
L20	0	(wet etch\$3 or wet-etch\$3) near10 (20% adj (water or "h. sub.2")) near10 (hydroxide\$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:36
L21	0	(wet etch\$3 or wet-etch\$3) near10 (10% adj (water or "h. sub.2")) near10 (hydroxide\$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:36
L22	3	(wet etch\$3 or wet-etch\$3) near10 (25% near3 (water or "h.sub.2")) near10 (hydroxide \$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:36
L23	9	("4465549" "5064498" "5071510" "5086011" "6168960" "6352871").PN. OR ("6428718").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:38
L24	2950	develop\$3 near10 solvent near10 (methanol or ethanol)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 14:36
L25	65	((("257".clas.) or ("438".clas.)) and develop\$3 near10 solvent near10 (methanol or ethanol)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 14:36
L26	9	(becker-gregory or gardner-geoffrey or harkness-brian).in.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 14:56

L27	9	(becker-gregory or gardner-geoffrey or harkness-brian). in.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 14:56
S1	2	"20060286809"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:38
S2	219	((organopolysiloxane or organo-polysiloxane) near10 average near10 silicon near10 alkenyl)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:51
S3	1556	((organosilicon or organo-silicon) near10 hydrogen)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:51
S4	5272	(catal\$4 near10 (hydrosilylation or hydrosilylation))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:52
S5	258469	(solvent near10 (alcohol or monoether or diether or aprotic))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:55
S6	100049	(base near10 hydroxide)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:55
S7	47	(solvent near10 anol)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:56
S8	246656	(solvent near10 (methanol or ethanol or propanol or isopropanol or butanol))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:56
S9	1407186	(rework or clean\$3)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:57
S10	1	S2 and S3 and S4 and S5 and S6 and S8 and (negative near10 (photoresist or photoresist or photo resist or resist)) and (heat\$3 or bak\$3) and radiat\$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:59

S11	26503	organopolysiloxane	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:09
S12	22624	organosilicon	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:10
S13	1	S11 and S12 and S4 and S5 and S6 and S8 and (negative near10 (photoresist or photoresist or photo resist or resist)) and (heat\$3 or bak\$3) and radiat\$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:11
S14	0	organopolysiloxane same organosilicon same hydrosilylat\$4 same (heat\$3 or bak\$3) same (etch\$3)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:12
S15	4	"549691".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:32
S16	2	"5496961".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:32
S17	1	"5591622".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:36
S18	2	"4585836".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:37
S19	2	"4584355".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:37
S20	2	"4530879".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:37

S21	2	"4510094".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:38
S22	2	"20020158317"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:39
S24	1	"6617674".pn.	USPAT	ADJ	ON	2008/03/06 09:46
S31	2	2002/0094671	USPAT	ADJ	ON	2008/03/06 09:49
S32	34	("20020094671" "4610079" "4670088" "5143865" "5496775" "5554887" "5703406" "5824569" "5834843" "5844779" "5867417" "5908317" "5933713" "5950070" "5969426" "5977641" "6020629" "6054772" "6077380" "6097098" "6107164" "6137164" "6150717" "6153448" "6181569" "6208018" "6297553" "6331450" "6368896" "6379999" "6499216" "6531341" "6780747" "6900074").PN. OR ("7183191").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:49
S33	3	2003/0027373	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:50
S34	3	2002/0115236	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:51
S35	2	2002/0094671	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:51
S36	7	2002/0063332	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:52
S37	1	"6433440".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:53
S38	1	"565885".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:54
S39	1	"5678301".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:54
S40	0	(negative near10 (photoresist or photo-resist or photo resist or resist)) same (organopolysiloxane) same (organosilicon) same (hydrosilylat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 10:03

S41	0	(photoresist or photo-resist or photo resist or resist) same (organopolysiloxane) same (organosilicon) same (hydrosilylat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 10:04
S42	111	(organopolysiloxane) same (organosilicon) same (hydrosilylat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 10:05
S43	9	("257".clas. or "438".clas.) and (organopolysiloxane) same (organosilicon) same (hydrosilylat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 10:05
S44	3	"6810585".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 10:06
S45	0	("2003/0214051").URPN.	USPAT	ADJ	ON	2008/03/06 10:08
S46	2	"1041117"	USPAT	ADJ	ON	2008/03/06 10:21
S47	1	"6239378".pn.	USPAT	ADJ	ON	2008/03/06 10:22
S48	1	"6083774".pn.	USPAT	ADJ	ON	2008/03/06 10:22
S49	1	"6369185".pn.	USPAT	ADJ	ON	2008/03/06 10:24
S50	202	((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat\$4 or irrdiat\$4) same (heat\$3 or bak\$3) same (develop\$3) same (etch\$3)	USPAT	ADJ	ON	2008/03/06 11:31
S51	7615050	((@pd< "20030728" or @ad< "20030728")	USPAT	ADJ	ON	2008/03/06 11:34
S52	180	S50 and S51	USPAT	ADJ	ON	2008/03/06 11:35
S53	69	((("257".clas.) or ("438".clas.)) and S52	USPAT	ADJ	ON	2008/03/06 11:37

S54	0	((((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat\$4 or irrdiat\$4) same (heat\$3 or bak\$3) same (develop\$3 near20 (methanol or propanol or butanol)) same (etch\$3 near20 (alcohol or monoether or diether or aprotic) near20 (hydroxide \$1))))	USPAT	ADJ	ON	2008/03/06 11:43
S55	1	((((negative) near10 (photoresist or resist or photo resist or photo-resist)) and (UV or ultraviolet or violet or radiat\$4 or irrdiat\$4) and (heat\$3 or bak\$3) and (develop\$3 near20 (methanol or propanol or butanol)) and (etch\$3 near20 (alcohol or monoether or diether or aprotic) near20 (hydroxide \$1))))	USPAT	ADJ	ON	2008/03/06 11:45
S56	28317	(negative) near10 (photoresist or resist or photo resist or photo-resist)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 11:49
S57	578562	(UV or ultraviolet or violet or radiat\$4 or irrdiat\$4)	USPAT	ADJ	ON	2008/03/06 11:50
S58	1461595	(heat\$3 or bak\$3)	USPAT	ADJ	ON	2008/03/06 11:50
S59	8989	(develop\$3 near20 (methanol or propanol or butanol))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 11:51
S60	360	(etch\$3 near20 (alcohol or monoether or diether or aprotic) near20 (hydroxide \$1))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 11:51
S61	0	(etch\$3 near20 (alcohol or monoether or diether or aprotic) near20 (hydroxide\$1) near20 phosphazene)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 11:53
S62	1	S56 and S57 and S58 and S59 and S60	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 11:54

S63	19929	(develop\$3 near20 (alcohol or methanol or propanol or butanol))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:11
S64	360	(etch\$3 near20 (alcohol or monoether or diether or aprotic) near20 (hydroxide\$1 or phosphazene))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:12
S65	3	S66 and S67 and S68 and S63 and S64	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:13
S66	11111	(develop\$3 near20 (methanol or propanol or butanol or ethanol))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:26
S67	21758	(develop\$3 near20 (methanol or propanol or butanol or ethanol or alcohol))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:27
S68	3	S66 and S67 and S68 and S67 and S64	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:28
S69	96	S66 and S67 and S68 and develop\$3 and etch\$3 and rework\$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:34
S70	87	S61 and S69	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:34
S71	383	((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat\$4 or irrdiat\$4) same (heat\$3 or bak\$3) same (develop\$3) same (etch\$3)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:37
S72	0	((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat\$4 or irrdiat\$4) same (heat\$3 or bak\$3) same (develop\$3) same (etch\$3) same rework\$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:38

S73	0	((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat\$4 or irrdiat\$4) same (heat\$3 or bak\$3) same (develop\$3) same (etch\$3) same rework	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:38
S74	157	((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat\$4 or irrdiat\$4) same (heat\$3 or bak\$3) same (develop\$3) same (etch\$3) same (additional or subsequent or multiple or second)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:39
S75	71	S74 and S51	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:42
S76	22	((("257".clas.) or ("438".clas.)) and S75	USPAT	ADJ	ON	2008/03/06 13:43
S77	755	(remov\$3 or etch\$3 or develop\$5) near10 (organic solvent) near10 (base)	USPAT	ADJ	ON	2008/03/06 16:30
S78	10	(remov\$3 or etch\$3 or develop\$5) near20 ((organic solvent) near10 (alcohol or monoether or diether or aprotic or polar)) near20 ((base) near10 (ammoni\$4 or hydroxide\$1 or phosphazene))	USPAT	ADJ	ON	2008/03/06 16:34
S79	18	(remov\$3 or etch\$3 or develop\$5) near20 ((organic solvent) near10 (methanol or ethanol)) near20 ((base) near10 (ammoni\$4 or hydroxide\$1 or phosphazene))	USPAT	ADJ	ON	2008/03/06 16:57
S80	14	S79 not S78	USPAT	ADJ	ON	2008/03/06 16:57
S81	0	(remov\$3 or etch\$3 or develop\$5) near20 ((organic solvent) near10 (methanol or ethanol)) near20 ((base) near10 (ammonium hydroxide))	USPAT	ADJ	ON	2008/03/06 17:16
S82	180	((base) near10 ((ammonium hydroxide\$1 near5 tretra) or phosphazene))	USPAT	ADJ	ON	2008/03/06 17:23

S83	1	("257".clas. or "438".clas.) and ((base) near10 ((ammonium hydroxide\$1 near5 tetra) or phosphazene))	USPAT	ADJ	ON	2008/03/06 17:24
S84	27	((base) near10 ((ammonium hydroxide\$1 near5 tetra) or phosphazene)) same (etch\$3 or remov\$3 or develop\$3)	USPAT	ADJ	ON	2008/03/06 17:24
S85	26	S84 and S51	USPAT	ADJ	ON	2008/03/06 17:25
S86	2	"6362116".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:12
S87	2	"5856065".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:12
S88	2	"5470693".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:22
S89	8285	develop\$3 near10 (methanol or ethanol)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:25
S90	14987032	((@pd<"19900728" or @ad<"19900728")	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:25
S91	3077	S89 and S90	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:26
S92	4238343	((@pd<"19700728" or @ad<"19700728")	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:26
S93	62	S89 and S92	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:26

S94	135	("257".clas. or "438".clas.) and S89	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:27
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